



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application of

Applicants : Jigish D. Trivedi  
Serial No. : 08/915,658  
Filed : August 21, 1997  
Title : LOW RESISTANCE METAL SILICIDE LOCAL INTERCONNECTS  
AND A METHOD OF MAKING  
Docket No. : MIO 0024 PA  
Examiner : G. Peralta  
Art Unit : 2814

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James E. Beyer

39,564  
Reg. No.

Sir:

RESPONSE

This paper is being filed in response to the Office Action of February 10, 2000. Reconsideration of the present application is respectfully requested in light of the remarks below.

REMARKS

Claims 31-40 are currently under consideration in the present application.

In the Office Action of February 10, 2000, claims 31-34 have been rejected under 35 U.S.C. § 102(b) as being anticipated by Okamoto (U.S. Patent 4,910,578). Claims 35-40 have been rejected under 35 U.S.C. § 103 (a) as being unpatentable over Okamoto in view of Shepard (U.S. Pat. 5,227,333).

Independent claim 31 recites a local interconnect comprising a first metal silicide, a second metal silicide, and an intermetallic compound comprising metal from said first metal silicide and metal from said second metal silicide. Independent claim 35 further